

UNIC-CASS Mentoring Session

2025-2026 Progress Questionnaire Results

Presented by: D-to-T mentoring team

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UNIC-CASS Page

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<https://unic-cass.github.io/>

Universalization of
IC Design in CASS

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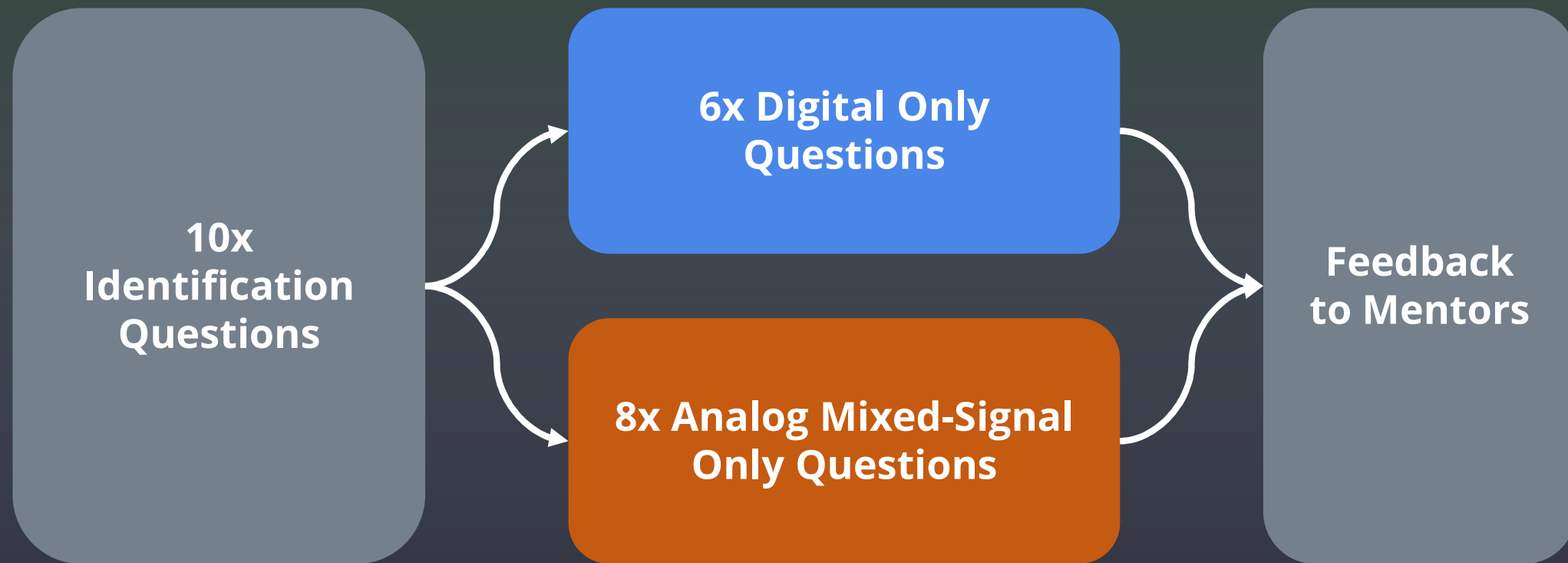
Track Team Progress Towards Tape-out

- Monitor each team's milestones
- Identify bottlenecks early to ensure teams stay on track for tape-out

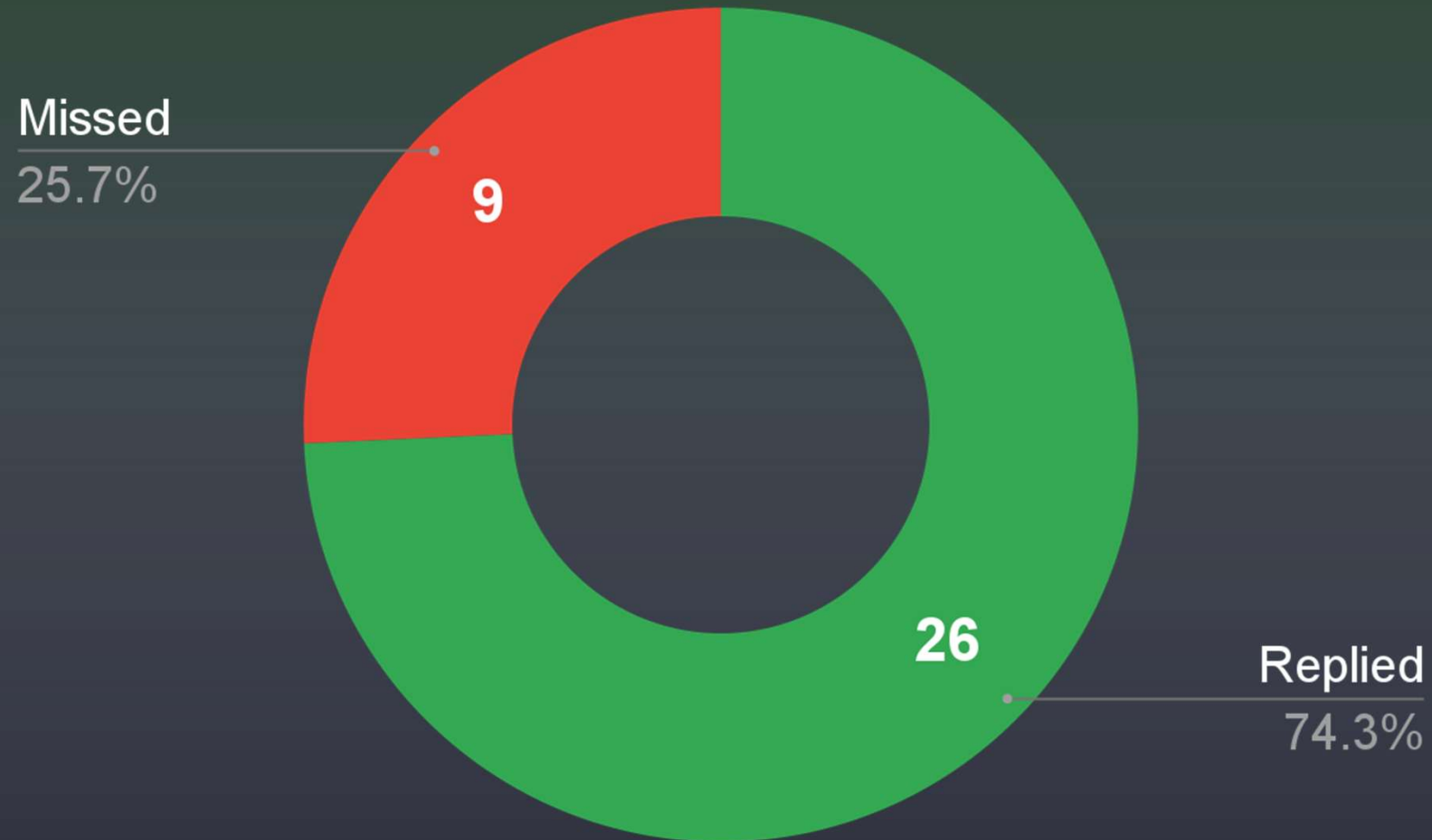
Refine and Improve the Program

- Ensure that training, tools, and resources meet the evolving needs of participants
- Gather feedbacks to improve this and future programs

Progress Questionnaire



Number of Teams that Filled the Progress Questionnaire





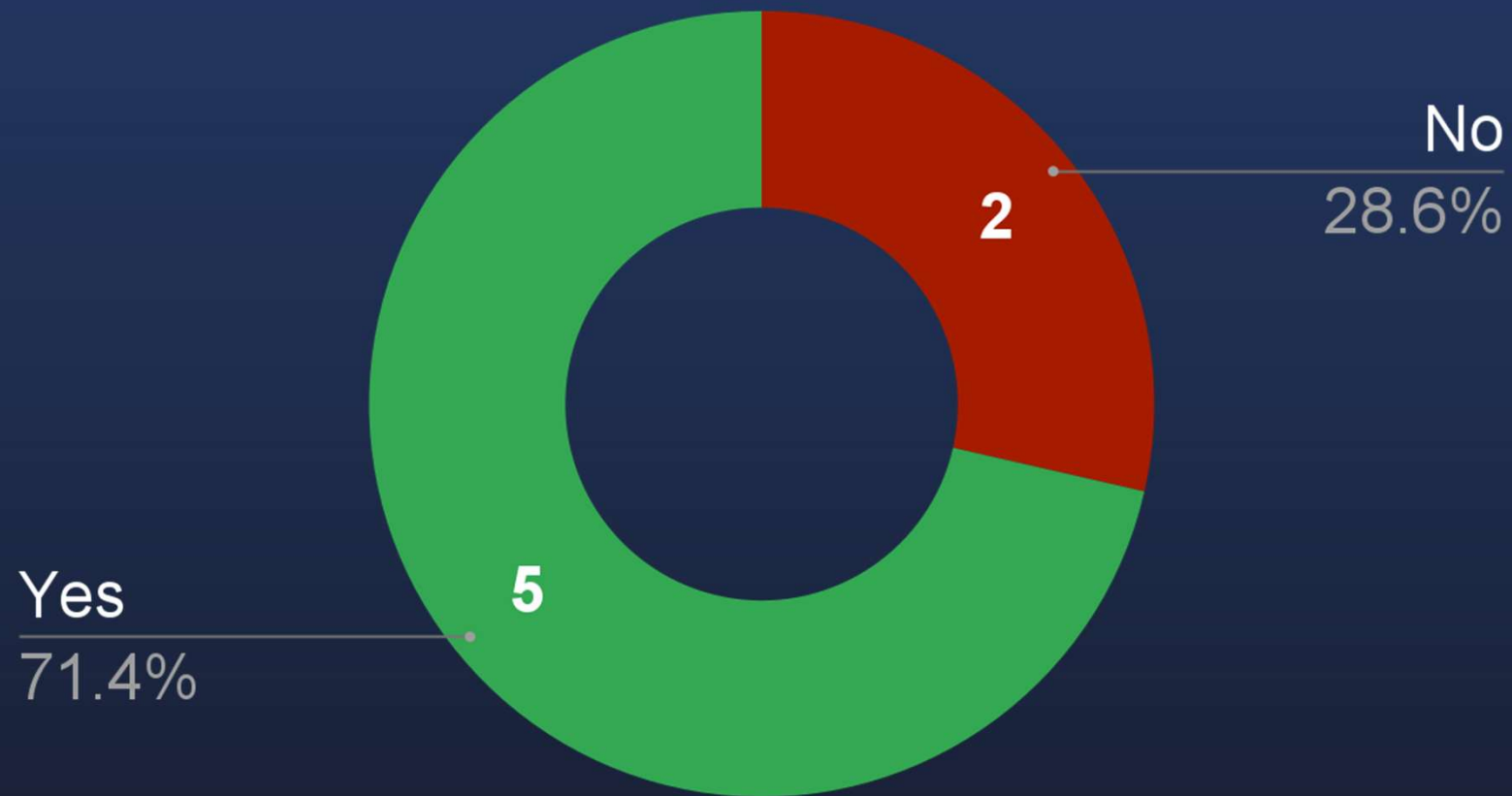
Distribution of Designs



Digital-Specific Questionnaire Results

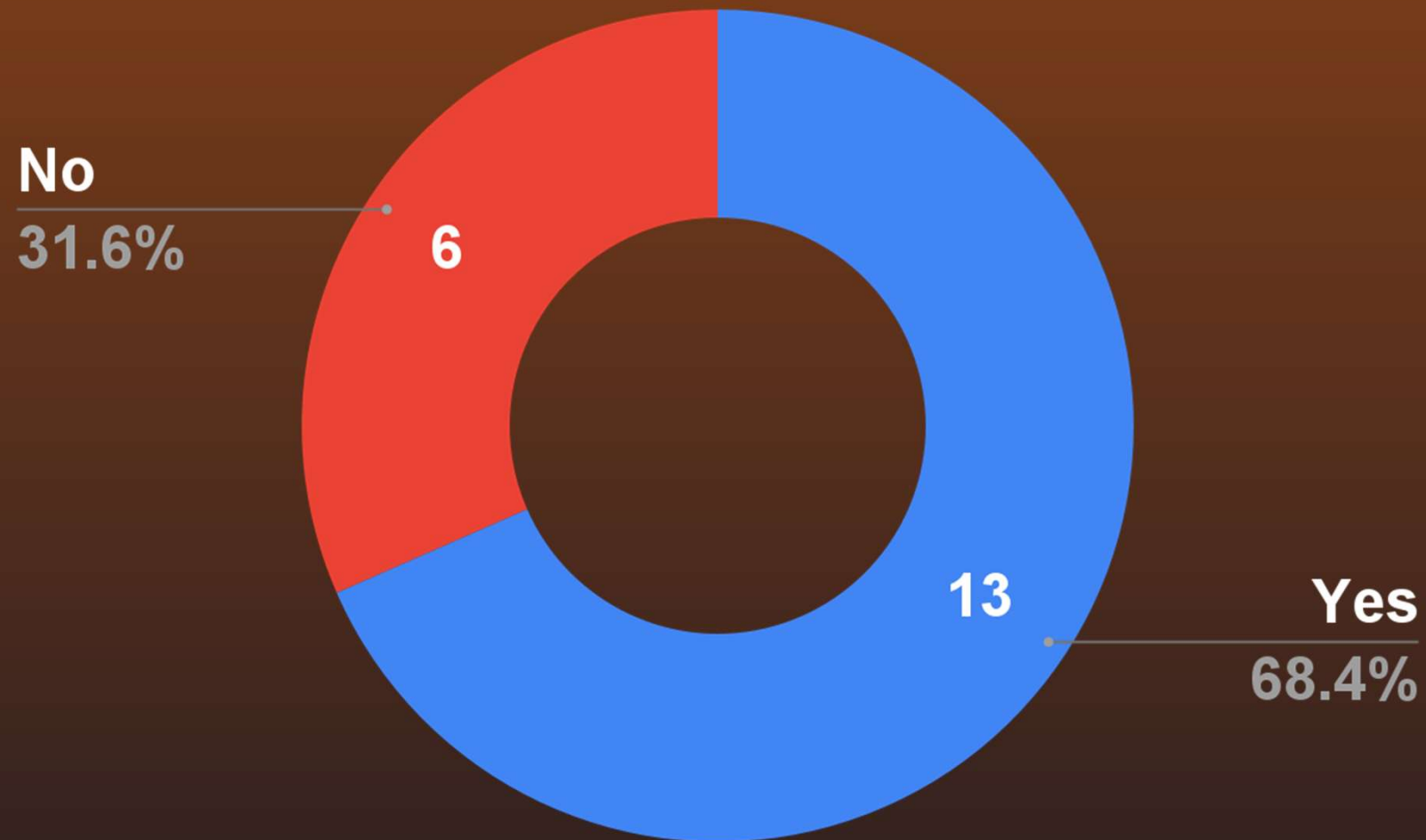
Number of Teams that Completed the RTL2GDSII Flow

RTL2GDSII



AMS-Specific Questionnaire Results

Number of Teams that Completed the Circuit Schematic



Feedback from UNIC-CASS Designers

16 Feedback Answers

(out of the 26 answers)

Feedback from Digital Designers

- 1. Add an end-to-end tutorial covering full project customization and the complete EDA flow
- 1. Simplify and unify tool installation/documentation, especially for users new to GitHub/Docker
- 1. Provide guidance for designs that are too complex for limited computing resources
- 1. Keep the current documentation and community support, which were positively rated

Feedback from AMS Designers

- 1. More content on post-layout simulation (PEX, multi-corner, AMS flows with open tools)
- 1. Hands-on layout sessions (KLayout/Magic), including good practices and top-level integration
- 1. Deeper coverage of DRC–LVS–PEX, including padding LVS and IO-pad simulations
- 1. Guidance on AMS-specific layout topics (e.g. inductors, parasitics, IO-cells)
- 1. Methodologies for transistor sizing (W/L), e.g. LUT-based approaches
- 1. Clearer organization and submission timelines
- 1. Overall feedback highlights the program as a unique and highly valuable opportunity, especially for underrepresented regions



UNIC-CASS Progress Questionnaire Results

